

List of Accepted Papers: 2026 EUVL and Source Workshop and Blue-X TWG Annual In-Person Meeting

Paper #	Day #	Session #	#	Session Name	First Name	Last Name	Company	Abstract title
B10	1	1	1	Blue-X sub TWG Update	Vivek	Bakshi	EUV Litho	Blue-X TWG: Status and Plans
B4	1	2	2	Blue-X Keynote	Takeo	Watanabe	University of Hyogo	The Lithographic Benefit and Technical Issue of Shortening the Wavelength of EUVL
B1	1	2	3	Blue-X Keynote	Ralph	Dammel	Merck / EMD Electronics	Dose Requirements for LCDU Control at Blue-X Wavelengths
B3	1	2	4	Blue-X Keynote	Yuri	Ralchenko	UMD	Overview of Atomic Spectroscopic Data for the Blue-X Water Window Program
B2	1	2	5	Blue-X Keynote	Vladimir	Liberman	MIT LL	Robust Design and Material Optimization for Multilayer Coatings for Blue Wavelengths
B46	1	3	1	Blue-X-Optics	TBA			Blue-X ML Optics Sub - TWG Update
B45	1	3	2	Blue-X-Optics	Marcelo	Ackermann	University of Twente	TBA
B43	1	3	3	Blue-X-Optics	Naoki	Hayase	University of Hyogo	Improved Mo2N/B multilayer for beyond EUV lithography
B44	1	3	4	Blue-X-Optics	Takeo	Ejima	University of Osaka	Deposition System for Reflective Multilayers below 6.x nm Enabled by Sub-nm Thickness Control
B41	1	3	5	Blue-X-Optics	Eric	Gullikson	LBNL	ML Project Update (Tentative Title)
B42	1	3	6	Blue-X-Optics	Ladislav	Pina	Rigaku	Grazing Incidence Mirror for FEL Water Window Beams
B67	1	4	1	Blue-X-Source	TBA			Blue-X Plasma Sources Sub - TWG Update
B63	1	4	2	Blue-X-Source	Yusuke	Teramoto	Ushio	Short-wavelength radiation from a regenerative target laser-produced plasma source

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B66	1	4	3	Blue-X-Sources	Mariko	Yamaguchi	RIC	Laser-driven, high brilliance sources in the BEUV to Tender X-ray range
B65	1	4	4	Blue-X-Source	Tommy	Sebastian	MIT LL	Development and Testing of Liquid Nitrogen Droplet Generator
B61	1	4	5	Blue-X-Source	Yosuke	Honda	KEK	FEL Development Status Update
B64	1	4	6	Blue-X-Source	Brandon	Holybee	xLight	Impact of EUV FEL Exposure on Photoresist Sensitivity and Chemical Mechanisms
B21	1	5	1	Blue-X-Mask	Meng / Ben	Lee / Eynon	Veeco / Lam	Blue-X Mask Sub - TWG Update
B22	1	5	2	Blue-X-Mask	Marcus	Benk	CXRO	SHARP photomask imaging: supporting the extension of EUV lithography beyond 0.55NA and 13.5nm wavelength
B32	1	6	1	Blue-X-Metrology	TBA			Blue-X ML Optics Sub - TWG Update
P33	1	6	2	Blue-X-Metrology	Victor	Soltwisch	PTB	Infrastructure for the water window: Status and future of optical metrology
B31	1	6	3	Blue-X-Metrology	Ben	Zeiger	Luxel	Transmission filters for <13.5 nm lithography
B52	1	7	1	Blue-X - Resist and Patterning	TBA			Blue-X Resist Sub - TWG Update
B51	1	7	2	Blue-X - Resist and Patterning	Dario	Goldfarb	IBM	Interactions of Polarized EUV Light with Resist

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P1	2	1	1	Keynote	Allen	Gabor	IBM	Beyond High-NA EUV: A Dose-Window Framework for Stochastic Integrity at Future Nodes
P2	2	1	2	Keynote	Vineet	Vijayakrishnan Nair	Micron	Mask Wafer Co Optimization for High NA EUV Readiness in Advanced DRAM
P76	2	2	1	Source -1	Oscar	Versolato	ARCNL	TBA
P74	2	2	2	Source -1	Hakaru	Mizoguchi	Kyushu university	EUV Exposure for Photo-Chemical Materials and LPP-EUV Source Research for Semiconductor Manufacturing II
P78	2	2	3	Source -1	Arun	Davaraj	PNNL	ANGEL project highlights (Tentative Title)
P77	2	2	4	Source -1	Kentaro	Tomita	Hokkaido University	Control of the Ion Energy Distribution Function in Double-Pulse Laser-Produced EUV Plasmas
P75	2	2	5	Source -1	Tirtha	Joshi	UCSD	Scaling of EUV Conversion Efficiency with Material and Laser Intensity in High-Z Plasmas
P71	2	2	6	Source -1	Mats	Brinkman	ARCNL	Broadband EUV Imaging Spectrometry
P79	2	2	7	Source -1	Owen	Bardeen	UC San Diego	Pulse Conditioning and Material Comparisons for Optimized EUV and Beyond-EUV Emission from Laser-Produced Plasmas
P72	2	3	1	Source -2	David	Reisman	Energetiq	EQS-10: A Next-Generation DPP EUV Light Source
P73	2	3	2	Source -2	Tomoyoshi	Toida	Gigaphoton	Development of Sn-LPP EUV Light Source for Actinic Mask Inspection
P80	2	3	3	Source -2	Hideyuki	Sera	Ushio	Comparative collective Thomson scattering study of single and dual-trigger LDP tin plasmas in an EUV source
P47	2	4	1	Resist and Patterning -1	Anuja	DeSilva	Lam	Dry Patterning Solutions Enabling High NA Lithography for Accelerated Feature Scaling

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P53	2	4	2	Resist and Patterning -1	Stacey	Bent	Stanford	Molecular layer deposition of metal coordination polymer resists for EUV lithography
P52	2	4	3	Resist and Patterning -1	Satinder	Sharma	SCEE/SCS	Iodine Functionalized Metal-Organic Cluster EUV Resists for High-Resolution Patterning with Fab-Compatible Processing
P51	2	4	4	Resist and Patterning -1	Iacopo	Mochi	PSI	Interference Lithography at EUV and Beyond at the XIL-II beamline
P50	2	4	5	Resist and Patterning -1	Ryan	Miyakawa	LBNL	TBA
P95	2	5	1	Supplier Showcase	Analía	Herrero	PTB	Soft X-rays for the inspection of complex nanostructures and thin layers
P93	2	5	2	Supplier Showcase	Jacqueline	van Veldhoven	TNO	EUV-generated plasma characterization using a transparent RFEA
P94	2	5	3	Supplier Showcase	Meng	Lee	Veeco	TBA
P92	2	5	4	Supplier Showcase	Henry	Chou	Energetiq	TBA
P91	2	5	5	Supplier Showcase	Matt	Hettermann	EUV Tech	Applications of EUV Metrology Tools
P101	2	6	1	Poster-Optics	Akira	Miyake	Toyama	The development of EUV and soft X-ray optical evaluation systems in TOYAMA
P102	2	6	2	Poster-Resist and Patterning	Hyun-Dam	Jeong	Chonnam National University	T4(THP)4: Exploring Silicon-Based Inorganic Molecular Resists for Blue-X (6.7 nm) Lithography
P103	2	6	3	Poster-Resist and Patterning	Hayun	Kim	Chonnam National University	Dynamic Covalent Assembly(DCA)-Zinc Oxo Cluster Resists for EUV, Blue-X (6.7 nm) and Blue-X (3.1 nm) Lithography

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P104	2	6	4	Poster-Resist and Patterning	Seungyong	Baek	Chonnam National U	Synthetic and Process Optimization of the Tin-Oxo Cluster CNU-TOC-01 toward Improved EUV Lithographic Performance
P105	2	6	5	Poster-Resist and Patterning	Hyun-Sung	Yoon	Chonnam National U	CASILON: A Core-Arm Siloxane Molecular Resist Candidate for Blue-X (6.7 nm) Lithography
P106	2	6	6	Poster-Resist and Patterning	Kenneth	Gonsalves	Indian Institute of Technology	Photoresists Beyond EUV: Revisiting X-ray Nanocomposite Resists - For Potential BEUVL
P107	2	6	7	Poster-Source	Wooram	Kim	Institute of Standards and	Tabletop Extreme Ultraviolet (EUV) Testing Platform for Lithography Materials
P108	2	6	8	Poster-Source	Kyu Chang	Park	Kyung Hee University	Performance of EUV Light Source with Cold Field Emitters (CFEs) Beam Irradiation Technique
P109	2	6	9	Poster-Source	Matthew	Polek	PNNL	Dynamics of pre-pulsed laser-produced plasmas generated using mass limited Sn targets
P110	2	6	10	Poster-Source	Stanislav	Musikin	PPPL	Multi-diagnostic experimental characterization of laser-produced tin plasmas

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P3	3	7	1	Keynote -2	Ronald	Goossens	ASML	The amazing longevity of Moore's Law - 50 years of progress in Lithography
P4	3	7	2	Keynote -2	Laura	Waller	UC Berkeley /BETR Center	Computational Microscopy for EUV Lithography
P26	3	8	1	and Mask Metrology	Sebastian	Brueck	Carl Zeiss	Advancements in ZEISS EUV Projection Optics: Enhancing Productivity and Enabling Shrink
P23	3	8	2	and Mask Metrology	Binyamin	Rubin	Veeco	In situ monitoring during Mo-Si Multilayer Deposition for EUV Mask Blanks : Concept and Simulation
P21	3	8	3	and Mask Metrology	Ayumi	Moriya	Hoya	Development of capping films integrated with mask process for 1.X nm node EUV blanks
P24	3	8	4	and Mask Metrology	Stuart	Sherwin	EUV Tech	Harnessing the Power of Actinic Metrology for EUV Masks
P25	3	8	5	and Mask Metrology	Luke	Long	EUV Tech	TBA
P22	3	8	6	and Mask Metrology	Zachary	Levinson	Synopsys	Accurate Long Range Compact Modeling for Low-NA and High-NA EUV Mask Solutions
P27	3	8	7	and Mask Metrology	Dong Gun	Lee	E-Sol	Integrated Actinic EUV Tool for Mask Review, Reflectometry, High-speed CD, and Phase Measurement
P34	3	9	1	Metrology	Ahmed	Diallo	PPPL	SparkLight: A New Platform for Laser-Produced Plasma Research in Support of Next-Generation EUV Lithography
P31	3	9	2	Metrology	Stephanie	Moffitt	NIST	New Developments at the Synchrotron Ultraviolet Radiation Facility (SURF III)
P32	3	9	3	Metrology	Brian	Simonds	NIST	Progress on the NIST Deployable Absolute EUV Radiometer
P33	3	9	4	Metrology	Jiho	Kim	Pohang/POSTECH	Actinic EUV/Blue-X Characterization for Advanced Materials and Lithography Applications

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P85	3	10	1	Source - Modeling	Igor	Golovkin	Prism Computations	Atomic Data and Collisional-Radiative Atomic Kinetics Simulations for EUV/x-ray Sources
P81	3	10	2	Source - Modeling	John	Sheil	ARCNL	TBA
P82	3	10	3	Source - Modeling	James	Colgan	LANL	Effective temperature approximations for use in modeling non-LTE tin plasmas
P83	3	10	4	Source - Modeling	Mark	Sherlock	LLNL	Quantum effects in the absorption of laser light by EUV-source relevant plasmas
P84	3	10	5	Source - Modeling	Kirill	Lezhnin	PPPL	Simulating fast ion debris for next-generation light sources for nanolithography
P86	3	10	6	Source - Modeling	Akira	Sasaki	QST	Investigation of atomic processes and radiative transfer in tin plasmas for updating the opacity table
P87	3	10	7	Source - Modeling	Nozomi	Tanaka	University of Osaka	Optimization of EUV output by experimentally validated radiation-hydrodynamic simulations across a broad laser parameter space

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P14	4	11	1	Lasers	Jens	Brunne	Trumpf	Scaling Efficiency and Power in CO ₂ Drive Lasers for EUV
P16	4	11	2	Lasers	Emily	Sistrunk Link	LLNL	High energy solid-state $\lambda \approx 2 \mu\text{m}$ laser drivers for efficient EUV and plasma sources
P11	4	11	3	Lasers	Tobias	Heuermann	AFS	2 μm fiber lasers as efficient next generation EUV drive lasers
P15	4	11	4	Lasers	Joachim	Gräfe	Trumpf	A Scalable 2 μm Laser Platform for Next Generation EUV Light Sources
P13	4	11	5	Lasers	Ryo	Yasuhara	for Fusion Science, Japan	Development of a High-Power 3–4 μm Mid-Infrared Laser for High-Efficiency EUV Light Sources
P12	4	11	6	Lasers	Robert	Klas	Fraunhofer IOF	Power Scalable Highly Efficient High Harmonic Generation at 13.5 nm Using a Visible-Driving Laser
P17	4	12	1	Accelerator (LWFA)	Finn	Kohrell	LBNL	Compact Free-Electron Lasing at BELLA Center's Laser-Plasma Accelerator
P18	4	12	2	Accelerator (LWFA)	Manuel	Kirchen	Elektronen-Synchrotron DESY	Laser-Plasma Accelerators and Their Potential to Drive EUV Light Sources
P19	4	12	3	Accelerator (LWFA)	Stephen	Milton	TAU Systems	TAU Systems Inc.: Bringing Laser-Powered Accelerator Systems to the Commercial Market
P20	4	12	4	Accelerator (LWFA)			TBA	TBA
P55	4	13	1	Resist and Patterning -2	Takahiro	Kozawa	University of Osaka	Development of Resist Materials under JST K Program
P42	4	13	2	Resist and Patterning -2	Chang-Yong	Nam	Brookhaven National Lab	EUV Research Activities and Infrastructure Development at BNL (Invited)
P48	4	13	3	Resist and Patterning -2	Ricardo	Ruiz	LBNL	TBA

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P46	4	14	1	Resist and Patterning -3	Michael	Tsapatsis	John Hopkins University	Amorphous Zeolitic Imidazolate Frameworks (aZIF) as Resists for EUV and BEUV Lithography
P54	4	14	2	Resist and Patterning -3	Congque	Dinh	TEL	Holistic Integration of Novel Patterning Technologies for High-NA EUV Lithography
P49	4	14	3	Resist and Patterning -3	Samuel	Blau	LBNL	Automated Reaction Network Construction and Spatiotemporal Kinetic Simulation
P56	4	14	4	Resist and Patterning -3	Kyunghyeon	Lee	University of Chicago	Design of block copolymers for directed self-assembly to mitigate stochastic challenges in EUV lithography
P45	4	14	5	Resist and Patterning -3	Jiwon	Kim	Hanyang Univ/CH3IPS	Defect-Free EUV Patterning of Metal Oxide Resists using Cl ₂ /Ar LET Plasma Dry Development for High-Fidelity Etch Transfer
P57	4	14	6	Resist and Patterning -3	Jiyoung	Kim	UT Dallas	Dry Developing Process of Molecular-Atomic-Layer-Deposited Hybrid Dry Photoresist for EUV Lithography
P41	4	14	7	Resist and Patterning -3	Nikhil	Tiwale	BNL	Positive-tone hybrid EUV resists synthesized by vapor phase infiltration